

# Uncertainty in Large-Signal Measurements Under Variable Load Conditions

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**Abstract**—We investigate the uncertainty of large-signal measurements of a microwave transistor due to variation in the load conditions at the fundamental frequency. In particular, we evaluate uncertainties in the complex frequency-domain traveling voltage waves. In our analysis, uncertainty sources typical for large-signal measurements are considered. Then, we discuss how the resultant uncertainty in the waves is dependent on a varying load reflection coefficient. For this investigation, we consider total uncertainty of the waves as well as its magnitude and phase. We also show that these errors unavoidably affect uncertainty of performance quantities, like output power.

**Index Terms**—Calibration, large-signal measurements, load-pull, measurement uncertainty, sensitivity analysis, vector network analyzer

## I. INTRODUCTION

LOAD-PULL measurements [1] extend large-signal measurement systems [2], [3] by changing the load conditions of a device under test (DUT). The most common setup only sets load impedance at the DUT excitation signal's fundamental frequency  $f_0$ . However, variants are also available that can control load conditions at harmonically related frequencies of  $f_0$ , usually at the second and third harmonic. A number of methods have been introduced over the years for setting the reflection coefficients. These solutions are based on both active [4], [5] and passive [6] load tuning. Moreover, a wideband load-pull system that is capable of controlling reflection coefficients for a modulated signal has been recently proposed [7]. Measurements taken with those setups can be used for a variety of purposes, including device modeling [8],

model validation [9], and design of high-performance power amplifiers (PAs) [10].

Knowing the uncertainty in measurements is particularly important for achieving first pass microwave circuit design success [9], [11]. By using results with relevant uncertainties, it is possible to estimate whether a project is likely to be successful with only one development iteration. As load-pull measurements gain popularity, it is of great importance to provide microwave circuit designers with data on how credible the load-pull results are. This may result in speeding up the design process and shortening the time between an idea and a product release.

While the uncertainty in large-signal measurements has been extensively investigated [12]–[16], including time-domain waveform uncertainties, [16], there has been relatively little work on evaluating the uncertainty in load-pull measurements. The attempts [17], [18] have so far focused on power-related figures of merit, like power-added efficiency (PAE) or gain, derived from these measurements. Uncertainty in the actual waves at the device's terminals was not considered. Furthermore, focus was only on the uncertainty of figures of merit in relation to the magnitude of the reflection coefficient  $\Gamma_L$  whereas its phase was not considered.

In this paper, we evaluate the uncertainty in the DUT's complex complex frequency-domain traveling voltage waves while considering both the magnitude and the phase of the load reflection coefficient. To achieve this goal, we performed extensive measurements and followed strict calibration schemes. We delineate sources of uncertainty in large-signal measurements and derive how they are included during a two-tier vector calibration using the Microwave Uncertainty Framework (MUF) developed at the National Institute of Standards and Technology (NIST) [19]. Next, we describe the measurement system used for taking load-pull measurements as well as a method for choosing load reflection coefficients. Finally, we evaluate uncertainty in the DUT's frequency-domain waves.

## II. UNCERTAINTY ANALYSIS OF LARGE-SIGNAL MEASUREMENTS

Evaluating measurement uncertainty is a complex challenge where many sources of errors, both random and systematic, must be included. By using the NIST MUF, we were able to consider uncertainties of the passive calibration standards, power meter, NIST traceable phase calibration reference [20],

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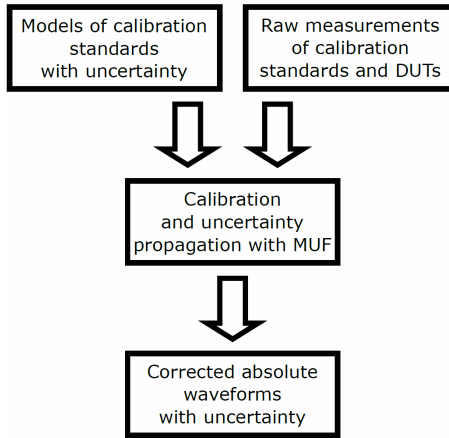


Fig. 1. Calibration procedure when using the MUF [16]

cable bending, coaxial connector repeatability [21], probe alignment, and even random errors [22] in our analysis. It is, however, worth noting that the MUF is not the only software package that can be used for estimating uncertainty in microwave measurements [23].

Despite so many error sources contributing to the uncertainty in large-signal measurements, including uncertainties due to the harmonic phase reference (HPR) remains the most challenging task. The HPR is used for re-establishing phase relationships between waves measured at harmonically related frequencies. Its characterization relies on a multi-step procedure. First, an impulse response of a photodiode is measured with an electrooptic sampling system [24]. Then, this device is used to determine the impulse response of a sampling scope [25] with mismatch correction applied [26]. Finally, characterization of the HPR must be performed [27] [28]. Hence, performing a full procedure is very cumbersome and requires highly qualified personnel and, to the best knowledge of the authors, NIST is the only research institute that has harmonic phase references characterized with correlated uncertainty as a measurement service.

Knowing the uncertainty in the HPR's output signal, it is possible to perform an uncertainty analysis of large-signal measurements. It is important to stress that we do not actually measure the uncertainties. They are estimated based on the characteristics of the calibration standards. To do so, measurements of calibration standards along with their statistical models must be processed by the MUF, see Fig. 1. Thanks to such an approach, all the predefined error sources, such as those listed above, are propagated through the large-signal calibration procedure. As a result, we receive calibration coefficients identified with perfect calibration standards as well as the range within which we could expect the coefficients if the definitions of the standards are imperfect. We can investigate how the error sources impact the calibration by performing either a sensitivity or a Monte Carlo analysis. The former investigates how each error source individually affects the final correction terms while the latter considers all the errors simultaneously and perturbs the calibration coefficients accordingly. Finally, the coefficients are used to correct the raw DUT measurements and identify their ideal and error-

perturbed values. An analogous procedure also applies to small-signal measurements.

Even though methods for computing uncertainty in large-signal measurements have already been established, there has been no thorough uncertainty analysis of frequency-domain waves and how it translates to uncertainty of figures of merit derived with these results. Moreover, how the uncertainty in those waves are affected by changing load conditions has not been examined. Such a procedure is performed in this paper.

In this paper, we employed the NIST MUF to perform sensitivity analysis and compute relevant uncertainty quantities. We chose this approach instead of the Monte Carlo simulations since the latter does not let us investigate the impact of the individual error sources on the final uncertainty results. Using typical notation for a two-port device, we define  $a_1$  and  $b_1$  as incident and scattered complex frequency-domain traveling voltage waves at port 1, while  $a_2$  and  $b_2$  are incident and scattered waves, respectively, at port 2. Since the port 2 waves are directly affected by changing load conditions, they are the focus of this section. We can compute the wave's covariance matrix, which gives us uncertainty of real and imaginary parts as well as the correlation between them. The waves are assumed to be linear combinations of  $n$  error sources, which we consider in our uncertainty analysis. For example, the  $b_2$  wave at the given frequency can be expressed as:

$$b_2 = f(\xi_1, \xi_2, \dots, \xi_n), \quad (1)$$

where variables  $\xi_n$  stand for error sources that can be traced to real variables, like the length of a calibration standard. The function  $f$  propagates all  $n$  errors through the large-signal calibration and gives a complex value of  $b_2$ .

All the physical error mechanisms may be grouped as an error vector  $\Xi$ . By assumption, they are uncorrelated to each other [12] and thus, their covariance matrix is diagonal:

$$\Sigma_{\Xi} = \begin{bmatrix} \sigma_{\xi_1}^2 & & \\ & \ddots & \\ & & \sigma_{\xi_n}^2 \end{bmatrix}. \quad (2)$$

The next step is calculating a Jacobian that provides us with information on how the wave responds to the individual error sources. For the purpose of this article, we separate how the errors affect real and imaginary parts of the waves. In the case of the  $b_2$  wave, we define its Jacobian  $J_{b_2}$  as:

$$J_{b_2} = \begin{bmatrix} \frac{\partial \Re(b_2)}{\partial \xi_1} & \dots & \frac{\partial \Re(b_2)}{\partial \xi_n} \\ \frac{\partial \Im(b_2)}{\partial \xi_1} & \dots & \frac{\partial \Im(b_2)}{\partial \xi_n} \end{bmatrix}. \quad (3)$$

Knowing the error vector's covariance matrix  $\Sigma_{\Xi}$  and the wave's Jacobian  $J_{b_2}$ , we can compute covariance matrix of the  $b_2$  wave:

$$\Sigma_{b_2} = J_{b_2} \cdot \Sigma_{\Xi} \cdot J_{b_2}^T, \quad (4)$$

which can be defined as:

$$\Sigma_{b_2} = \begin{bmatrix} \sigma_{\Re(b_2)}^2 & \sigma_{\Re(b_2)\Im(b_2)} \\ \sigma_{\Re(b_2)\Im(b_2)} & \sigma_{\Im(b_2)}^2 \end{bmatrix}, \quad (5)$$

where the diagonal terms are variances of the wave's real and imaginary parts while  $\sigma_{\Re(b_2)\Im(b_2)}$  stands for covariance between them.

Therefore,  $\sigma_{\Re(b_2)\Im(b_2)}$  provides us with the variance of the  $b_2$ 's real and imaginary parts as well as their dependence on each other. Using  $\Sigma_{b_2}$ , it is possible to derive additional quantities. We define the total variance of  $b_2$  as:

$$\sigma_{b_2}^2 = \lambda_1 + \lambda_2, \quad (6)$$

where  $\lambda_1$  and  $\lambda_2$  are eigenvalues of the  $b_2$ 's covariance matrix.  $\sigma_{b_2}^2$  could simply be interpreted as a sum of the real and imaginary components, however, (6) allows to account for  $\sigma_{\Re(b_2)\Im(b_2)}$  as well. Having identified the covariance matrix, it's also possible to compute uncertainty of the  $b_2$ 's magnitude

$$|b_2| = \sqrt{\Re(b_2)^2 + \Im(b_2)^2}. \quad (7)$$

Any change of  $|b_2|$  caused by shifts in  $\Re(b_2)$  and  $\Im(b_2)$  can be expressed as

$$d|b_2| = \frac{\partial |b_2|}{\partial \Re(b_2)} d\Re(b_2) + \frac{\partial |b_2|}{\partial \Im(b_2)} d\Im(b_2), \quad (8)$$

where the derivatives can be calculated in terms of:

$$\frac{\partial |b_2|}{\partial \Re(b_2)} = \frac{\Re(b_2)}{|b_2|}, \quad (9)$$

$$\frac{\partial |b_2|}{\partial \Im(b_2)} = \frac{\Im(b_2)}{|b_2|}. \quad (10)$$

The variance of  $|b_2|$  can be computed as the expected value of the change in the  $b_2$ 's magnitude squared

$$\sigma_{|b_2|}^2 = E\left((d|b_2|)^2\right). \quad (11)$$

Variations of  $\Re(b_2)$  and  $\Im(b_2)$  resulting in  $d|b_2|$  are substituted by standard deviations of the  $b_2$ 's real and imaginary parts, in which the covariance matrix  $\Sigma_{b_2}$  [1,2] also appears. The result is

$$\begin{aligned} \sigma_{|b_2|}^2 &= \left(\frac{\partial |b_2|}{\partial \Re(b_2)}\right)^2 \cdot \sigma_{\Re(b_2)}^2 + \\ &\left(\frac{\partial |b_2|}{\partial \Im(b_2)}\right)^2 \cdot \sigma_{\Im(b_2)}^2 + \\ &2 \cdot \frac{\partial |b_2|}{\partial \Re(b_2)} \cdot \frac{\partial |b_2|}{\partial \Im(b_2)} \cdot \sigma_{\Re(b_2)\Im(b_2)}. \end{aligned} \quad (12)$$

Subsequently, the uncertainty of the  $b_2$ 's phase is derived. We can compute  $\phi(b_2)$  with the following equation

$$\phi(b_2) = \arctan\left(\frac{\Im(b_2)}{\Re(b_2)}\right). \quad (13)$$

First, its change with regards to the varying  $\Re(b_2)$  and  $\Im(b_2)$  is

$$d\phi(b_2) = \frac{\partial \phi(b_2)}{\partial \Re(b_2)} d\Re(b_2) + \frac{\partial \phi(b_2)}{\partial \Im(b_2)} d\Im(b_2). \quad (14)$$

Computing partial derivatives of  $\phi(b_2)$ , we obtain

$$\frac{\partial \phi(b_2)}{\partial \Re(b_2)} = \frac{1}{1 + \left(\frac{\Im(b_2)}{\Re(b_2)}\right)^2} \cdot \frac{-\Im(b_2)}{\Re(b_2)^2}, \quad (15)$$

$$\frac{\partial \phi(b_2)}{\partial \Im(b_2)} = \frac{1}{1 + \left(\frac{\Im(b_2)}{\Re(b_2)}\right)^2} \cdot \frac{1}{\Re(b_2)}. \quad (16)$$

Finally, we can calculate the variance of the  $b_2$ 's phase as

$$\sigma_{\phi(b_2)}^2 = E\left((d\phi(b_2))^2\right) \quad (17)$$

When we expand the equation and consider the covariance between the real and imaginary parts of the  $b_2$  wave, we obtain

$$\begin{aligned} \sigma_{\phi(b_2)}^2 &= \left(\frac{\partial \phi(b_2)}{\partial \Re(b_2)}\right)^2 \cdot \sigma_{\Re(b_2)}^2 + \\ &\left(\frac{\partial \phi(b_2)}{\partial \Im(b_2)}\right)^2 \cdot \sigma_{\Im(b_2)}^2 + \\ &2 \cdot \frac{\partial \phi(b_2)}{\partial \Re(b_2)} \cdot \frac{\partial \phi(b_2)}{\partial \Im(b_2)} \cdot \sigma_{\Re(b_2)\Im(b_2)}. \end{aligned} \quad (18)$$

$\sigma_{a_2}^2$ ,  $\sigma_{|a_2|}^2$ , and  $\sigma_{\phi(a_2)}^2$  are calculated similarly. In the next sections, standard deviations will be used for discussing the uncertainty in the experiments performed.

Knowing the uncertainty in  $b_2$  and  $a_2$ , it is possible to investigate how their uncertainty affects figures of merit that represent the performance of microwave devices. As an example, we can derive uncertainty of the power delivered to the load  $P_{out}$  as

$$P_{out} = \frac{|b_2|^2 - |a_2|^2}{2Z_0}. \quad (19)$$

Since  $|b_2|$  and  $|a_2|$  directly affect  $P_{out}$ , they also define its uncertainty. To identify  $\sigma_{P_{out}}$ , we use an equation for computing the standard deviation of a generic parameter  $y$  dependent on  $N$  variables  $x$  [29]

$$\sigma_y = \sqrt{\sum_{i=1}^N \sum_{j=1}^N \frac{\partial f}{\partial x_i} \frac{\partial f}{\partial x_j} \sigma_{x_i x_j}}, \quad (20)$$

which can be further simplified if we assume the variables  $x$  are uncorrelated:

$$\sigma_y = \sqrt{\sum_{i=1}^N \left(\frac{\partial f}{\partial x_i}\right)^2 \sigma_{x_i}^2}. \quad (21)$$

Since this assumption is valid for magnitudes of the  $b_2$  and  $a_2$  waves [17], we derive the standard deviation of  $P_{out}$  as:

$$\sigma_{P_{out}} = \sqrt{\left(\frac{\partial P_{out}}{\partial |b_2|}\right)^2 \cdot \sigma_{|b_2|}^2 + \left(\frac{\partial P_{out}}{\partial |a_2|}\right)^2 \cdot \sigma_{|a_2|}^2}, \quad (22)$$

which simplified takes a form of

$$\sigma_{P_{out}} = \frac{\sqrt{|b_2| \cdot \sigma_{|b_2|}^2 + |a_2| \cdot \sigma_{|a_2|}^2}}{Z_0}. \quad (23)$$

This method of computing  $\sigma_{P_{out}}$  is a simplification. A Monte-Carlo approach can be used, but then it is not possible to track sources of error in the problem. Reference [29] suggests higher-order terms in the Taylor series expansion

should be included if the function is highly nonlinear. But even with this approach, tracking error sources will be imperfect due to the interaction of errors in the nonlinear function. In the case considered, it means a device generating non-negligible amount of power at higher harmonics. Nevertheless, the definition of the output power's standard deviation provided in (23) is sufficient to give microwave designers indication whether their circuit will conform to the design requirements. Furthermore, such an approach allows us to easily compare our results with relevant publications, like reference [17] that implies the uncertainty of  $P_{out}$  increases with the magnitude of the load reflection coefficient  $\Gamma_L$  for all its phases.

### III. LOAD-PULL MEASUREMENT SYSTEM

In this section, we present the set up used for performing load-pull measurements. The schematic diagram is shown in Fig. 2. A nonlinear vector network analyzer (NVNA) measured frequency-domain waves directly at the device's terminals. To achieve this on the DUT's output and avoid de-embedding of the passive tuner, we used a set of external couplers connected directly to the NVNA's receivers. In the figure, they are denoted as the output port reflectometer. An internal bias-tee of the network analyzer was used to set the DC voltage at the DUT's input. On the output side, an external bias-tee was located outside the passive tuner.

A mixer-based Keysight LSNA, PNA-X N5245A<sup>1</sup>, operating in the frequency range up to 50 GHz, was used for the large-signal measurements. The external output reflectometer consisted of two low-loss directional Marki CA-50<sup>1</sup> couplers and was connected to the output probe with a short cable. HP 4142B modular DC supplies<sup>1</sup> were used for setting the requested bias voltages at the input and output terminals of the DUT.

For the load-pull measurements, we used a Focus Microwave MPT-1818<sup>1</sup> passive tuner, which is capable of tuning up to three harmonics at frequencies between 1.8 and 18 GHz. However, we only used it to set load reflection coefficient at the fundamental frequency. We characterized the instrument with the manufacturer's software [30]. This is achieved by measuring the tuner's S-parameters in multiple tuning states. To ensure that the characterization procedure is valid, the measurements of the instrument must be very accurate. Thus, the NVNA was calibrated with the unknown *thru* scheme [31] due to its high accuracy. Gathered data and the reflection coefficient of the tuner's termination are used by the control software to accurately set  $\Gamma_T$  at the tuner's input. However, if reflection coefficients other than those used as the characterization tuning states are needed, interpolation methods are employed. However, any inaccuracies due to the operation of the tuning method can be ignored because the NVNA measures absolute waves and thus, we exactly know what reflection coefficient has been achieved.

Since the passive tuner is connected to the DUT through the output reflectometer, we needed to consider its characteristics

<sup>1</sup>Trade names are used here only to fully specify the experimental configuration and do not constitute an endorsement by NIST. Other instruments made by the same or different manufacturer may function as well or better for this application.

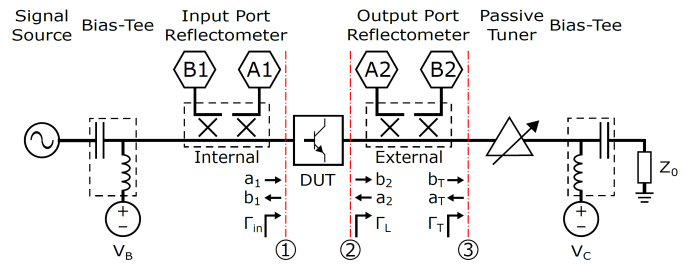


Fig. 2. Block diagram of a passive load-pull system used for experiments. A1, B1, A2, and B2 denote the internal receivers of the NVNA that measure the frequency-domain waves  $a_1$ ,  $b_1$ ,  $a_2$ , and  $b_2$ , respectively

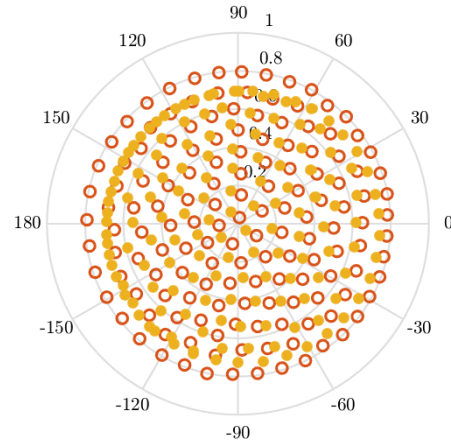


Fig. 3. Load reflection coefficients  $\Gamma_L$  identified by CVT (red circles) and measured (orange dots) at  $f_0 = 9$  GHz during experiments,  $P_{av} = 0$  dBm

while calculating  $\Gamma_T$  so as to provide the requested load reflection coefficient  $\Gamma_L$  at the output of the DUT, see Fig. 2. Due to this configuration, the reflectometer's losses limit the maximum  $|\Gamma_L|$ . Knowing the maximum magnitude of the reflection coefficient achievable by the tuner, which is around 0.92, as well as the total insertion loss of the external couplers and the on-wafer fixture, we decided to limit  $|\Gamma_L|$  to 0.8. Values of  $\Gamma_L$  to be measured were identified with Centroidal Voronoi Tessellation (CVT) [32] [33], which is a space division method that, in our case, ensures a uniform coverage of the Smith chart. Target load reflection coefficients are marked as orange dots in Fig. 3. For our experiments, we employed CVT to define 149 load reflection coefficients. This number of loads was chosen as a trade-off between the highly dense coverage of the Smith chart and the total measurement time.

Using the setup described, we performed large-signal measurements of state-of-the-art indium phosphide (InP) hetero-junction bipolar transistors (HBTs) manufactured by Teledyne Technologies<sup>1</sup> [34]. Their emitter is 250 nm wide. For our experiments, we used the transistors with 6  $\mu\text{m}$  long emitter. They were biased to achieve the collector current  $I_C = 6$  mA at the collector voltage  $V_C = 1.5$  V. This operating point was chosen to achieve high power gain when used in a power amplifier configuration at mmWave frequencies. Complex waves at four harmonics were measured with the fundamental frequency  $f_0 = 9$  GHz. Available input power  $P_{av}$  was set between -30 and 0 dBm. The reflection coefficient  $\Gamma_L$  was varied at  $f_0$



Table I  
SOLT CALIBRATION STANDARDS WITH ASSOCIATED STANDARD UNCERTAINTIES

General Characteristics	
Inner conductor diameter (mm)	1.042±0.004
Outer conductor diameter (mm)	2.400±0.005
Pin diameter (mm)	0.511±0.005
Offset Short and Open	
Line length (mm)	6.750±0.005
Offset Load	
Line length (mm)	7.700±0.005
Load resistance (Ω)	50.0±0.7
Load inductance (nH)	0.02±0.02

Table II  
TRL CALIBRATION STANDARDS WITH ASSOCIATED STANDARD UNCERTAINTIES. PARAMETERS L AND W ARE THE TRANSMISSION LINE'S LENGTH AND WIDTH, RESPECTIVELY. H IS THE SUBSTRATE'S THICKNESS

	Line 1	Line 2	Line 3
L (μm)	290±0.05	774±0.05	2000±0.05
W (μm)	11.6±0.05		
H (μm)	5±0.5		

Table III  
NOMINAL PHASES OF THE COMB GENERATOR ALONG WITH THEIR STANDARD UNCERTAINTIES

Frequency (GHz)	9	18	27	36
Phase (°)	169.5±0.5	160.2±0.6	152.0±0.9	148.2±1.0

over the points defined in the previous paragraph. Measured  $\Gamma_L$ , shown as orange dots in Fig. 3, is calculated using the following equation:

$$\Gamma_L = \frac{a_{2,nom}}{b_{2,nom}}, \quad (24)$$

where  $a_{2,nom}$  and  $b_{2,nom}$  are a frequency waves at the fundamental frequency  $f_0$  corrected with the nominal MUF calibration unperturbed by any simulated error sources. Despite limiting the magnitude of the load reflection coefficient, we observe that the measured  $\Gamma_L$  constellation is further compressed and off-center. It is particularly noticeable on the left side of the plot, for  $\phi(\Gamma_L)$  from to  $90^\circ$  or  $-90^\circ$  where  $|\Gamma_L|$  hardly reaches 0.7. On the opposite side, the magnitudes go up to 0.75. This shift may be attributed to the characterization of the tuner's termination, which consisted of a bias-tee and a 50 Ω load. Whereas the additional decrease of  $|\Gamma_L|$  is probably a result of the extra loss introduced by the short transmission lines connecting the transistors to the probe pads or our overestimation how high the magnitude of the tuner's reflection coefficient  $\Gamma_T$  at  $f_0$  may be achieved. The load impedance at the second harmonic  $2f_0$  was set to 50 Ω. Effectively, the magnitude of  $\Gamma_L$  at  $2f_0$  was within 0.3 while its phase varied. These load conditions can impact the uncertainty in the waves at the second harmonic. However, the correlation between frequency-domain waves at different frequencies was confirmed to be negligible. Therefore, the uncertainty in the waves at  $2f_0$  does not affect the results gathered at  $f_0$ .

Since the load-pull experiments were done on-wafer, a two-tier calibration procedure was executed. First, a Short-Open-Load-Thru (SOLT) [35] coaxial large-signal calibration was accomplished. Then, the NVNA was connected to the probe station and an on-wafer multilayer Thru-Reflect-Line (TRL) [36] [37] calibration was performed such that the reference planes could be moved to the device terminals. Therefore, both coaxial SOLT and on-wafer TRL standards had to be provided with uncertainty resulting from their imperfect physical parameters. TRL standards were manufactured on the same substrate as the DUTs. Raw measurements of all calibration standards, including the HPR and the power meter, were taken. They were used for performing an on-wafer large-signal calibration with the NIST MUF, as defined by a simplified flow chart shown in Fig. 1. Resultant correction coefficients were applied to uncalibrated measurements of the transistor.

All the error sources considered were propagated through the calibration procedure. Physical parameters and the associated standard uncertainties of the SOLT and TRL calibration artifacts are listed in Table I and II, respectively. The length of the on-wafer thru and reflect artifacts is 0. Moreover, models of the TRL standards include the repeatability of the probe positioning. The uncertainty of the left-to-right alignment is equal to  $\pm 20 \mu\text{m}$ . For including the possible cable bending errors, we took measurements of a thru on-wafer standard while changing the position of the cable. Furthermore, Tab. III reports the phases of the NIST-characterized comb generator [27] [28] along with their standard uncertainties at the frequencies relevant for the calibration procedure. Next, we accounted for the errors in the power meter measurements based on [38]. They stem from the reference oscillator mismatch, the reference oscillator power uncertainty, the zero-set error, the zero carry-over error, the instrumentation error, and error in the power sensor calibration factor. Finally, the HPR's and power meter's reflection coefficients were considered as well.

#### IV. UNCERTAINTY IN FREQUENCY-DOMAIN WAVES UNDER SMALL-SIGNAL CONDITIONS

Knowing how the measurements were performed, we can finally report results of frequency waves uncertainty analysis. First, we estimate the uncertainty in frequency-domain waves when the transistor operates under a small-signal regime, that is at  $P_{av} = -22 \text{ dBm}$ .  $\sigma_{b_2}$ , see Fig. 4, increases particularly quickly when  $\phi(\Gamma_L)$  is around  $30^\circ$ . The  $b_2$  standard deviation increases significantly slower outside this area of the load reflection coefficient and the lowest rate is when  $\phi(\Gamma_L)$  approaches  $-150^\circ$ .

Fig. 5a shows how the magnitude of the  $b_2$  wave is dependent on the changing reflection coefficient  $\Gamma_L$ . It achieves its maximum value when the magnitude of the reflection coefficient is high and its phase nears  $35^\circ$ . This is in line with our expectations where the InP transistors used for the experiments should achieve the highest magnitude of their output signal. Consequently,  $|b_2|$  steadily decreases towards the opposite side of the plot where  $\phi(\Gamma_L)$  approaches  $-145^\circ$ . The wave's standard deviation  $\sigma(|b_2|)$ , presented in Fig. 5b, acts similarly and has its maximum in the same region as the

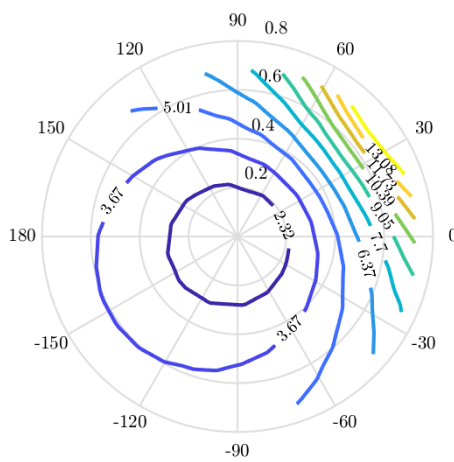
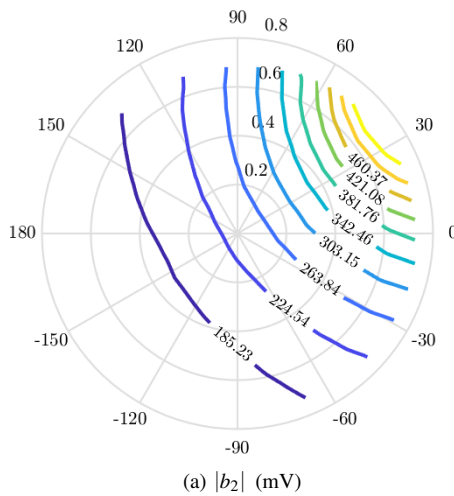
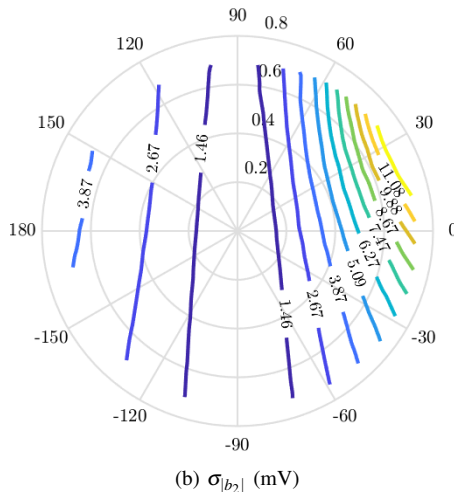


Fig. 4. Standard deviation of the  $b_2$  wave,  $\sigma_{b_2}$  (mV), at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm



(a)  $|b_2|$  (mV)

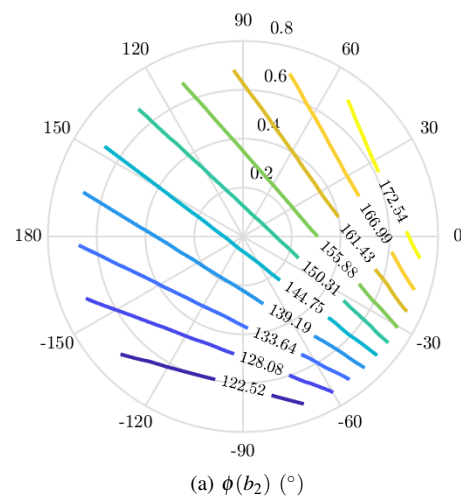


(b)  $\sigma_{|b_2|}$  (mV)

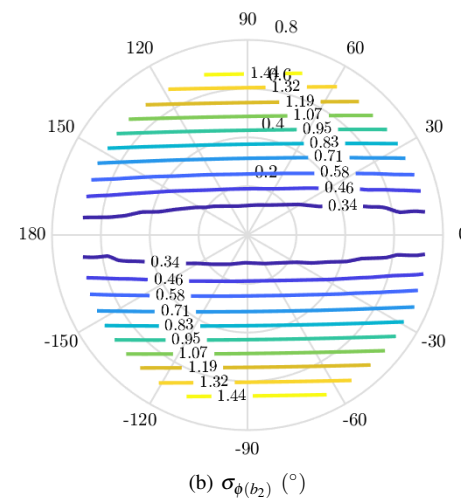
Fig. 5. (a) Magnitude of  $b_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm

$|b_2|$  wave. When  $\phi(\Gamma_L)$  is close to  $90^\circ$  or  $-90^\circ$ , the standard deviation of  $b_2$ 's magnitude is low. However, the magnitude's uncertainty slightly increases when  $\phi(\Gamma_L)$  is close to  $180^\circ$  and  $|\Gamma_L|$  raises.

Considering the  $b_2$  wave's phase, shown in Fig. 6a, we



(a)  $\phi(b_2)$  ( $^\circ$ )



(b)  $\sigma_{\phi(b_2)}$  ( $^\circ$ )

Fig. 6. (a) Phase of  $b_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm

observe that it gradually increases from the bottom towards the top right quarter of the plot. The standard deviation of the  $b_2$ 's phase, which is shown in Fig. 6b, rises towards the bottom and the top of the plot along the y-axis. While the load reflection coefficient's phase is around  $0^\circ$  and  $180^\circ$  degrees,  $\sigma_{\phi(b_2)}$  is practically unrelated to the  $\Gamma_L$ 's magnitude. Furthermore,  $\sigma_{\phi(b_2)}$ 's dependence on  $\Gamma_L$  practically rotates by  $90^\circ$  when compared with  $\sigma(|b_2|)$ .

The  $b_2$  wave's dependence on  $|\Gamma_L|$  and  $\phi(\Gamma_L)$  can be described as orthogonal and thus results in what is shown in Fig. 4. Therefore, even though we might at first have assumed that the standard deviation of the  $b_2$  is solely related to  $\Gamma_L$ 's magnitude, the actual dependence of  $b_2$  on the load reflection coefficient is more complex and both the magnitude and phase of  $\Gamma_L$  have to be considered.

When analyzing the standard deviation of the  $a_2$  wave, shown in Fig. 7, it clearly increases when  $\phi(\Gamma_L)$  is close to  $35^\circ$  and  $|\Gamma_L|$  is high.  $\sigma_{a_2}$  decreases towards the opposite end of the plot, that is where  $\phi(\Gamma_L)$  is close to  $-150^\circ$  and  $|\Gamma_L|$  is high. The behavior of  $\sigma_{a_2}$  is similar to  $\sigma_{b_2}$ , shown in Fig. 4. However, it's more concentrated around its maximum. Another noteworthy observation is the similarity between the  $\sigma_{a_2}$ 's contours and the behavior of the  $b_2$ 's magnitude, which can be seen in Fig.

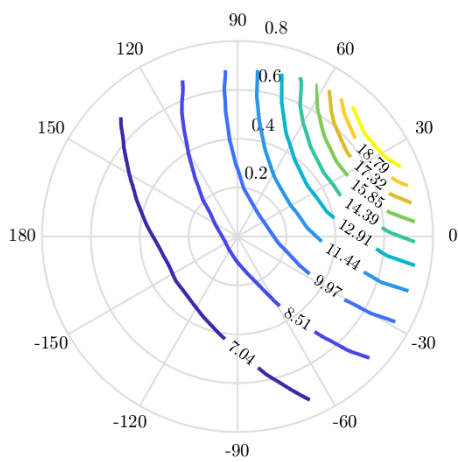
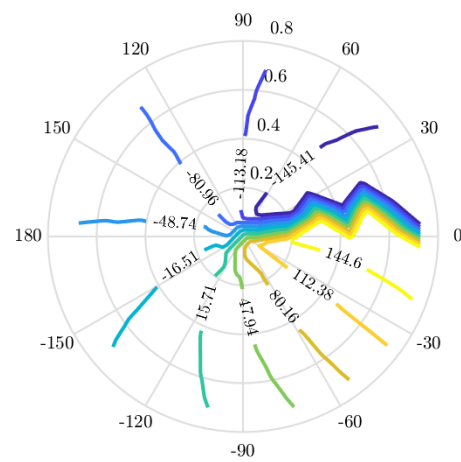
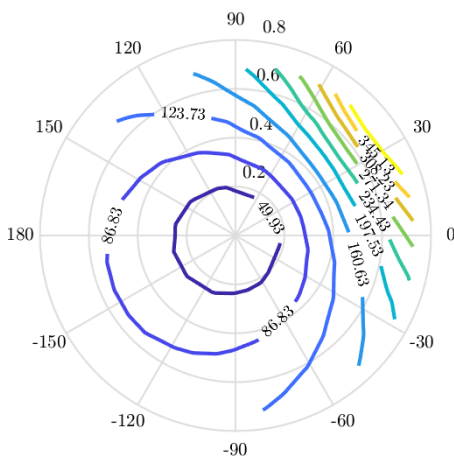


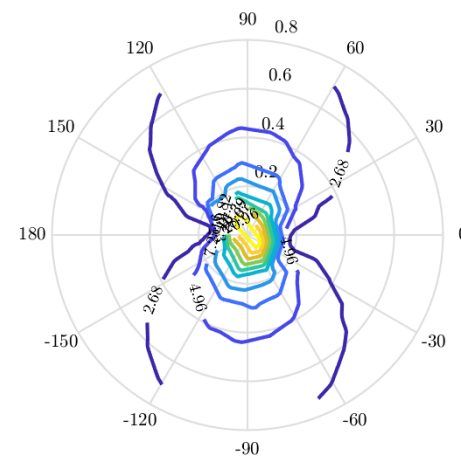
Fig. 7. Standard deviation of the  $a_2$  wave,  $\sigma_{a_2}$  (mV), at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm



(a)  $\phi(a_2)$  ( $^\circ$ )

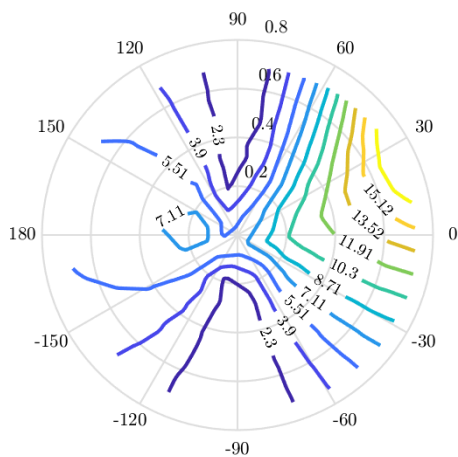


(a)  $|a_2|$  (mV)



(b)  $\sigma_{\phi(a_2)}$  ( $^\circ$ )

Fig. 9. (a) Phase of  $a_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm



(b)  $\sigma_{|a_2|}$  (mV)

Fig. 8. (a) Magnitude of  $a_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm

5a. Additionally,  $\sigma_{a_2}$  is higher than  $\sigma_{b_2}$ .

As expected, the magnitude of  $a_2$ , which is shown in Fig. 8a, follows  $|b_2|$ . However, its contours are very similar to the plot of  $\sigma_{b_2}$  from Fig. 4. Consequently,  $\sigma_{|a_2|}$ , see Fig. 8b, also follows the  $b_2$  wave and is largest when the phase of the load

reflection coefficient is close to  $25^\circ$  and the magnitude of  $\Gamma_L$  is around 0.7, just like  $\sigma_{|b_2|}$ . When  $\phi(\Gamma_L)$  is close to  $90^\circ$  and  $-90^\circ$ ,  $\sigma_{|a_2|}$  is small and further decreases when  $|\Gamma_L|$  rises. As  $\phi(\Gamma_L)$  nears  $180^\circ$ ,  $\sigma_{|a_2|}$  slightly increases. On top of this, we observe that  $\sigma_{|a_2|}$  is generally higher than  $\sigma_{|b_2|}$  at this input power level.

We also investigated the phase of the  $a_2$  wave, which is presented in Fig. 9a. Subsequently, Fig. 9b shows the standard deviation of  $\phi(a_2)$ , which is largest when the magnitude of  $\Gamma_L$  is small and rapidly decreases when it gets higher. The decrease rate is higher along the  $x$ -axis, that is when  $\phi(\Gamma_L)$  close to  $0^\circ$  or  $180^\circ$ . We suspect that the uncertainty of the  $a_2$ 's phase is highest in the middle of the plot due to low levels of  $|a_2|$ . This makes the measurements of  $a_2$  more susceptible to noise and other error sources. Thus, even slight changes of the real or imaginary parts of  $a_2$  can cause high variability of  $\sigma_{\phi(a_2)}$ .

Knowing the  $a_2$  and  $b_2$  waves and uncertainty of their magnitudes, it is possible to compute the device's output power  $P_{out}$  delivered to the load, see (19). Fig. 10a shows how  $P_{out}$  behaves when the reflection coefficient  $\Gamma_L$  changes.  $P_{out}$  achieves its maximum when  $|\Gamma_L|$  is about 0.7 while  $\phi(\Gamma_L)$  is close to  $35^\circ$ . For other reflection coefficients,  $P_{out}$  steadily

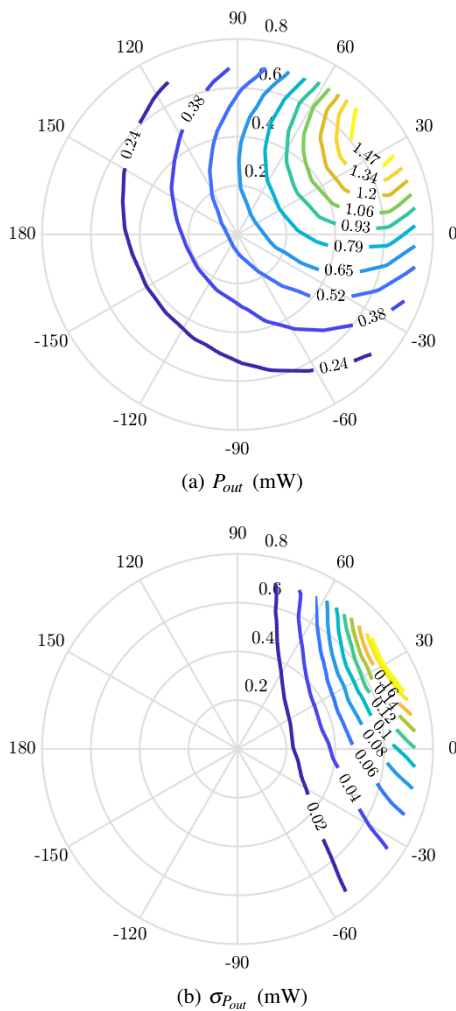


Fig. 10. (a) Output power  $P_{out}$  and its (b) standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = -22$  dBm

decreases. As expected, the output power closely follows the magnitude characteristics of the  $b_2$  and  $a_2$  waves shown in Fig. 5a and 8a, respectively.

If we consider the standard deviation of  $P_{out}$ , shown in Fig. 10b, we see that it reaches its maximum when  $|\Gamma_L|$  is around 0.7 and  $\phi(\Gamma_L)$  reaches  $30^\circ$ . Such a behavior could be expected based on plots of  $\sigma_{|b_2|}$  and  $\sigma_{|a_2|}$ , see Fig. 5b and 8b.

## V. UNCERTAINTY IN FREQUENCY-DOMAIN WAVES UNDER LARGE-SIGNAL CONDITIONS

Considering the device's behavior under large-signal conditions, at  $P_{av} = 0$  dBm, we observe very similar results to what was shown for the transistor working in the small-signal regime, that is at  $P_{av} = -22$  dBm. Looking at Fig. 11, we could conclude that the standard deviation of the  $b_2$  wave is simply proportional to the magnitude of the load reflection coefficient  $\Gamma_L$  while virtually independent of its phase. However, to completely understand this, it is necessary to analyze how the uncertainty of  $b_2$ 's magnitude and phase behave in relation to the changing load.

Starting with the characteristic of the  $b_2$ 's magnitude, see Fig. 12a, we observe that it steadily rises along the  $x$ -axis towards the *open* side of the plot, that is when  $\phi(\Gamma_L)$  close to

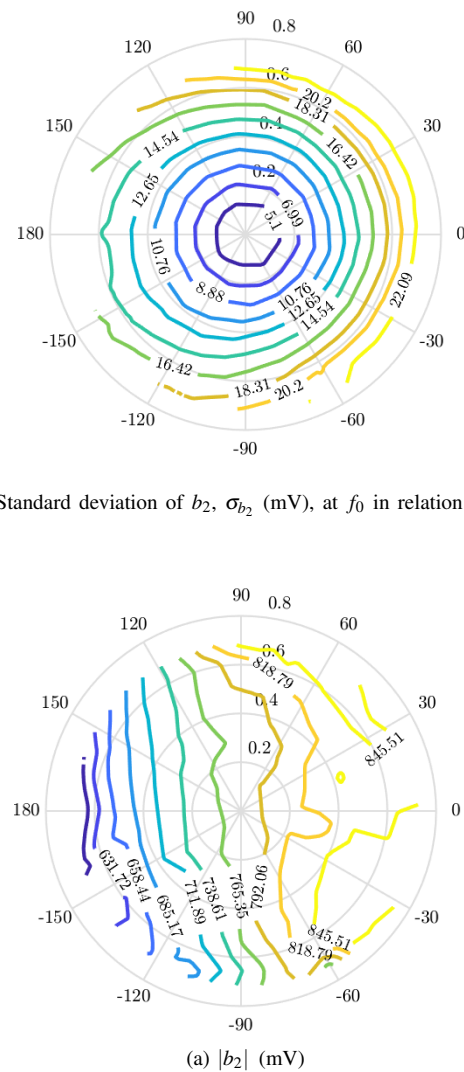


Fig. 11. Standard deviation of  $b_2$ ,  $\sigma_{b_2}$  (mV), at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

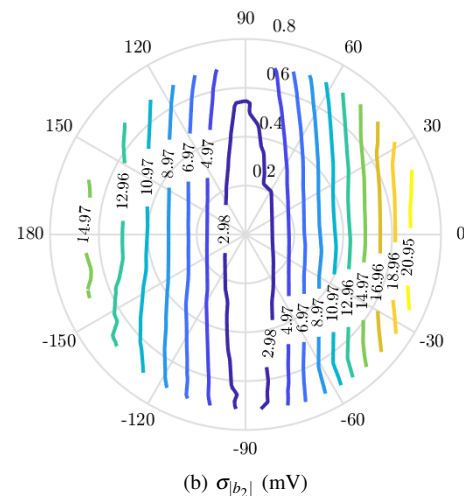


Fig. 12. (a) Magnitude of  $b_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

$0^\circ$  and  $|\Gamma_L|$  approaches 0.7. Next, Fig. 12b shows the standard deviation of the wave's magnitude  $\sigma_{|b_2|}$ , which increases with  $\Gamma_L$ 's magnitude but only when the phase of the reflection coefficient is close to  $0^\circ$  or  $180^\circ$ . The rate of the change is significantly higher in the right part of the plot. This aligns



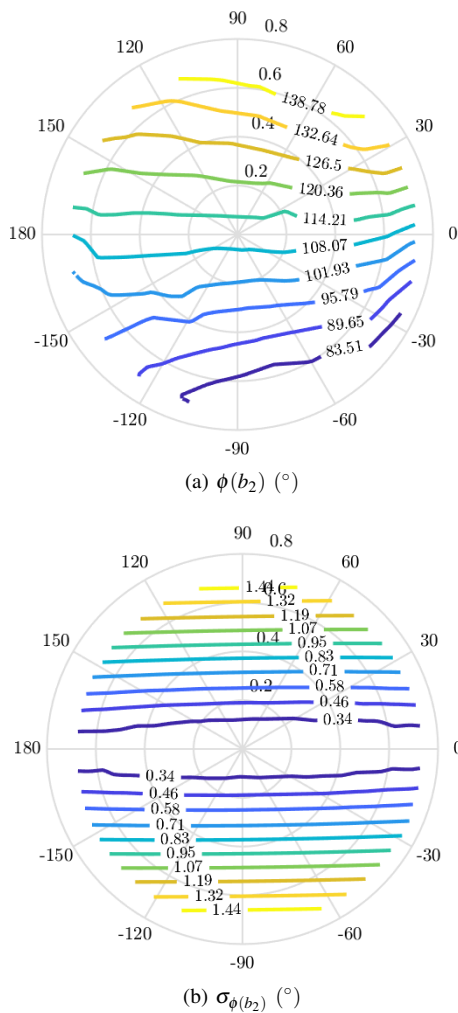


Fig. 13. (a) Phase of  $b_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

with the behavior of  $|b_2|$ . When the  $\Gamma_L$ 's phase gets close to  $90^\circ$  or  $-90^\circ$ ,  $\sigma_{|b_2|}$  is practically independent of  $|\Gamma_L|$ . Finally, it's noteworthy that  $\sigma_{|b_2|}$  acts similarly to its counterpart measured at  $P_{av} = -22$  dBm.

The phase of the  $b_2$  wave was investigated as well. Its graph is shown in Fig. 13a. It is highest as  $\phi(\Gamma_L)$  approaches  $75^\circ$  and  $|\Gamma_L|$  is high. Its lowest values are observed when  $\phi(\Gamma_L)$  is close to  $-60^\circ$ . However, considering the standard deviation of the  $b_2$ 's phase, shown in Fig. 13b, it is particularly noteworthy the characteristic of  $\sigma_{\phi(b_2)}$  is virtually identical to the characteristic of this parameter at  $P_{av} = -22$  dBm, see Fig. 6b, with just insignificant value differences.

Analyzing the  $a_2$  wave's uncertainty, sweeping the reflection coefficient over the specified area does not cause significant changes in the  $a_2$ 's standard deviation, shown in Fig. 14. Moreover, those changes are relatively smaller than in the case of the small-signal conditions, see Fig. 7. Nevertheless,  $\sigma_{a_2}$  steadily increases as  $\Gamma_L$  approaches open circuit conditions. Finally, the uncertainty of  $a_2$  closely follows the characteristic of the  $b_2$ 's magnitude, which is shown in Fig. 12b. Thus, the  $\sigma_{a_2}$ 's behavior under large-signal conditions is in line with its small-signal counterpart.

In Fig. 15a, we show the magnitude of  $a_2$  under changing

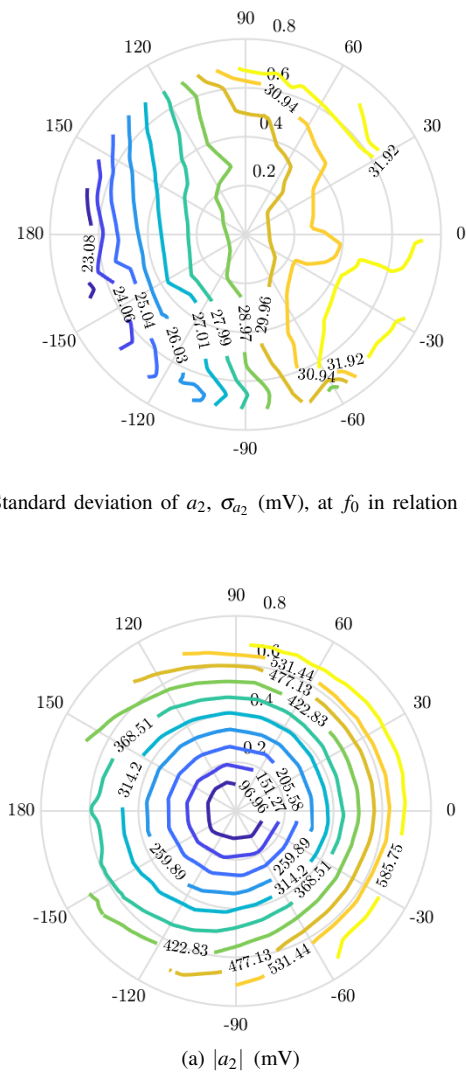


Fig. 14. Standard deviation of  $a_2$ ,  $\sigma_{a_2}$  (mV), at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

Fig. 15. (a) Magnitude of  $a_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

load conditions. As expected,  $|a_2|$  rises when  $|\Gamma_L|$ 's phase approaches the maximum values achievable by the measurement setup.  $|a_2|$  at  $P_{av} = 0$  dBm acts similarly to this wave's magnitude under small-signal conditions and thus, its contours are almost identical to  $\sigma_{b_2}$  in Fig. 11. The standard deviation of  $|a_2|$ , see

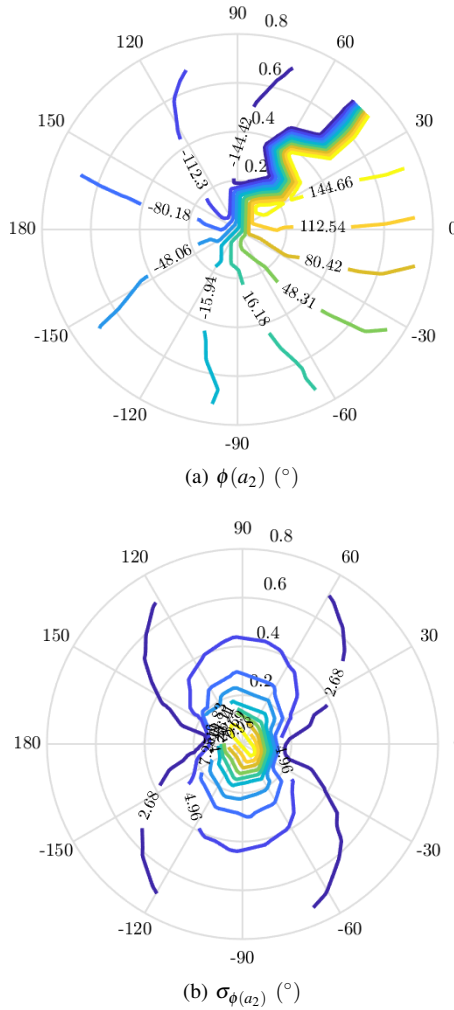


Fig. 16. (a) Phase of  $a_2$  and (b) its standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

Fig. 15b, achieves its maximum in the same region as  $\sigma_{|b_2|}$  from Fig. 12b.  $\sigma_{|a_2|}$  increases noticeably faster when  $\phi(\Gamma_L)$  is close to  $180^\circ$  in comparison to its small-signal counterpart in Fig. 8b. As before,  $\sigma_{|a_2|}$  is higher than  $\sigma_{|b_2|}$  at the same power level.

Fig. 16a shows the phase of  $a_2$  under large-signal conditions. Just like  $b_2$  at  $P_{av} = 0$  dBm,  $\sigma_{\phi(a_2)}$  has a very similar behavior to its counterpart when the DUT is excited with the small signal, see Fig. 16b and 9b, respectively.

As in the case of measurement under small-signal conditions, we can analyze  $P_{out}$  and its standard deviation. For  $P_{av} = 0$  dBm, we observe the maximum output power is achieved when  $|\Gamma_L|$  is 0.2 and  $\phi(\Gamma_L)$  equal to around  $0^\circ$ , see Fig. 17a. This is a significant change in comparison with the  $P_{out}$ 's behavior at  $P_{av} = -22$  dBm, shown in Fig. 10a.

$\sigma_{P_{out}}$ , see Fig. 17b, follows this change as it is highest when the phase of the reflection coefficient gets close to  $0^\circ$  and its magnitude is high. As in the small-signal case, this behavior could be expected if the uncertainty in the  $b_2$  and  $a_2$  waves's magnitudes are scrutinized, see Fig. 12b and 12b, respectively.

Figures of  $\sigma_{P_{out}}$  for two operation conditions undeniably show that when considering uncertainty of the device's figures

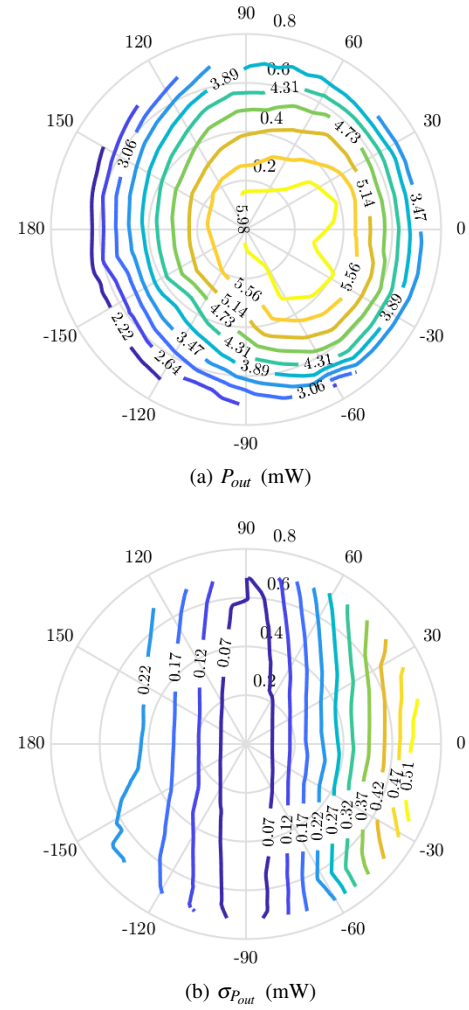


Fig. 17. (a) Output power  $P_{out}$  and its (b) standard deviation at  $f_0$  in relation to  $\Gamma_L$ ,  $P_{av} = 0$  dBm

of merit under changing load conditions, we need to analyze them in relation to both the magnitude and the phase of the load reflection coefficient. Otherwise, we lose important dependencies that may invalidate the design process.

## VI. JUXTAPOSITION OF SMALL- AND LARGE-SIGNAL CONDITIONS

For comparison, uncertainty in the DUT's  $b_2$  wave at two power levels, that is  $P_{av} = -22$  dBm and  $P_{av} = 0$  dBm, are displayed in the same figures. Fig. 18a presents standard deviation of the  $b_2$  wave with regards to the magnitude of the reflection coefficient. As already suggested by analyzing Fig. 11 and 4, there is seemingly a clear correlation between  $\sigma_{b_2}$  and  $|\Gamma_L|$ .

However, this assumption is invalidated by Fig. 18b, which shows dependence of  $\sigma_{|b_2|}$  on  $|\Gamma_L|$ . This plot shows that  $\sigma_{|b_2|}$  is not necessarily high when the magnitude of  $\Gamma_L$  increases. Moreover, Fig. 19a clearly shows that the standard deviation of  $b_2$ 's magnitude is strongly dependent on the phase of  $\Gamma_L$ . In Fig. 18a, we also observe the standard deviation of the  $b_2$  wave increases when the input power level rises. The same applies to  $\sigma_{|b_2|}$ , based on Fig. 18b and 19a.

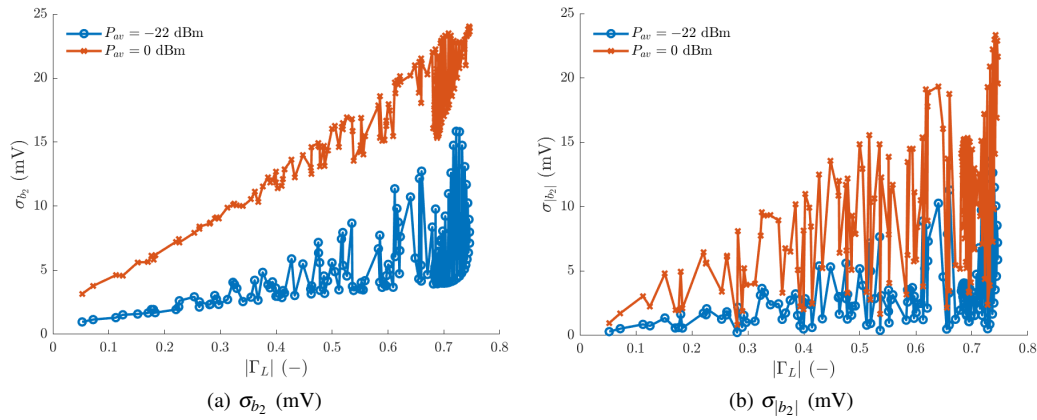


Fig. 18. Standard deviation of (a)  $b_2$  and its (b) magnitude in relation to  $|\Gamma_L|$ , for  $-180^\circ < \phi(\Gamma_L) < 180^\circ$

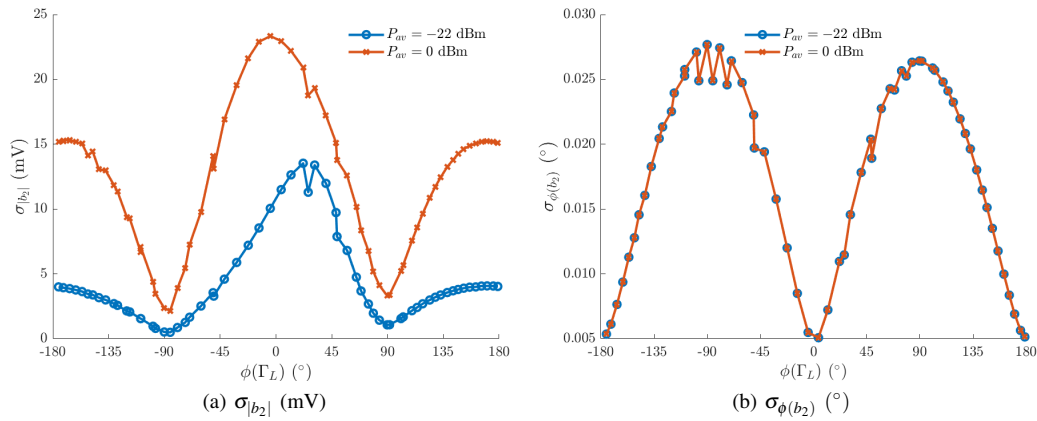


Fig. 19. Standard deviation of  $b_2$ 's (a) magnitude and (b) phase at  $f_0$  in relation to  $\phi(\Gamma_L)$ , for  $|\Gamma_L| \geq 0.65$

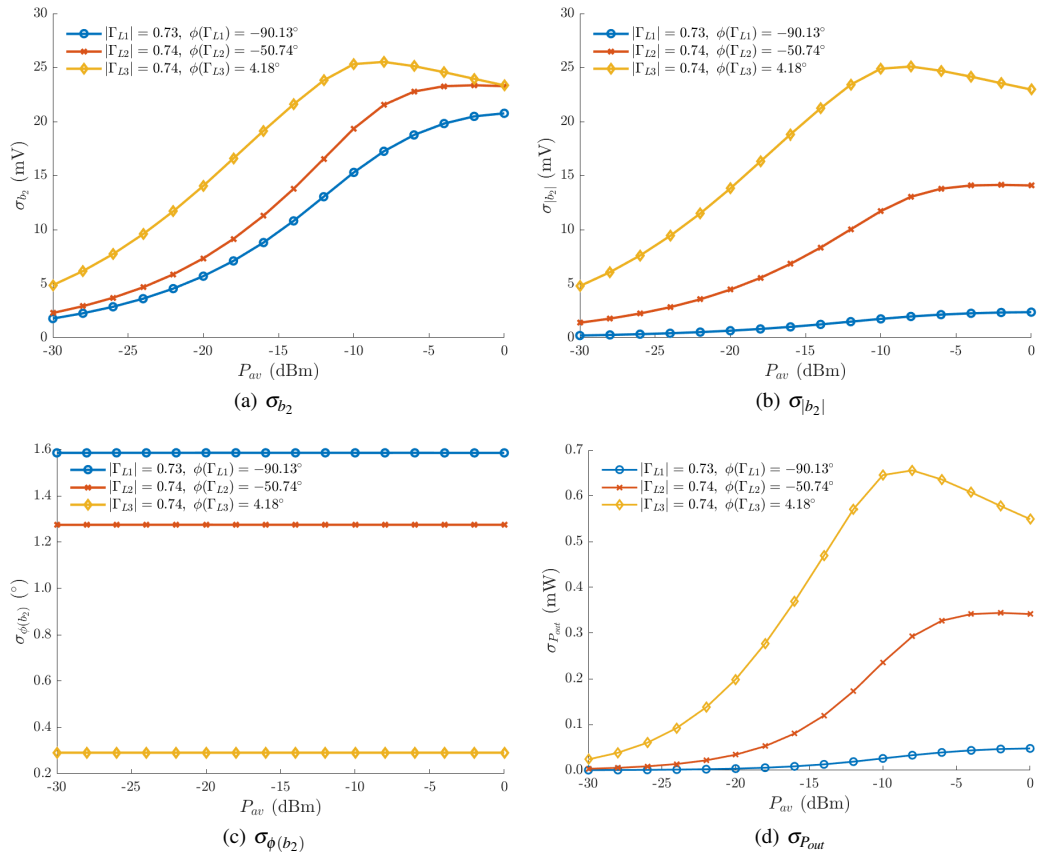


Fig. 20. Standard deviation of (a)  $b_2$ , its (b) magnitude and (c) phase at  $f_0$  as well as (d)  $P_{out}$  in relation to  $P_{av}$

Table IV  
TOTAL AND INDIVIDUAL UNCERTAINTY CONTRIBUTIONS IN THE MAGNITUDE AND PHASE OF THE  $b_2$  WAVE UNDER THREE DISTINCT LOAD CONDITIONS FOR  $P_{av} = 0$  dBm

	$ \Gamma_{L1}  = 0.73, \phi(\Gamma_{L1}) = -90.13^\circ$		$ \Gamma_{L2}  = 0.74, \phi(\Gamma_{L2}) = -50.74^\circ$		$ \Gamma_{L3}  = 0.74, \phi(\Gamma_{L3}) = 4.18^\circ$	
	$\sigma_{ b_2 }$ (mV)	$\sigma_{\phi(b_2)}$ ( $^\circ$ )	$\sigma_{ b_2 }$ (mV)	$\sigma_{\phi(b_2)}$ ( $^\circ$ )	$\sigma_{ b_2 }$ (mV)	$\sigma_{\phi(b_2)}$ ( $^\circ$ )
Total	2.467	1.584	13.938	1.291	22.963	0.291
TRL	1.731	1.559	13.696	1.270	22.896	0.133
SOLT	1.176	0.144	1.414	0.139	1.181	0.151
Power Meter	0.133	0.006	0.169	0.002	0.058	0.011
Comb Generator Repeatability	$5.904 \cdot 10^{-12}$	$2.054 \cdot 10^{-13}$	$7.045 \cdot 10^{-12}$	$2.943 \cdot 10^{-13}$	$5.218 \cdot 10^{-12}$	$3.484 \cdot 10^{-13}$
Comb Generator Characterization	$9.965 \cdot 10^{-11}$	$3.407 \cdot 10^{-12}$	$1.151 \cdot 10^{-10}$	$3.941 \cdot 10^{-12}$	$8.988 \cdot 10^{-11}$	$4.768 \cdot 10^{-12}$
Probe Alignment	0.756	0.173	0.743	0.179	0.394	0.184
Cable Bending	0.073	0.005	0.079	0.006	0.082	0.005

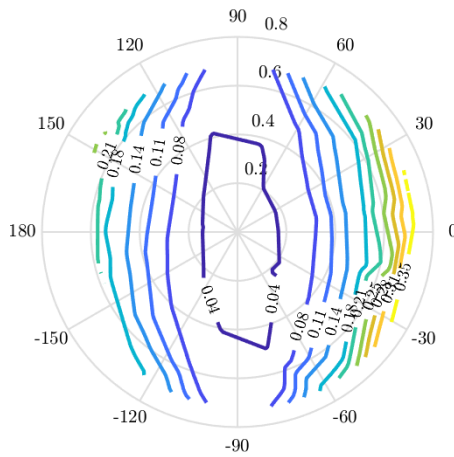


Fig. 21. Standard deviation of the output power  $P_{out}$  for a slice of  $P_{out}$  between 2.1 and 2.3 mW

On top of this,  $\sigma_{\phi(b_2)}$  also has a strong dependence on  $\phi(\Gamma_L)$  as displayed in Fig. 19b that confirms conclusions reached analyzing Fig. 13b and 6b. Since both traces practically overlap, Fig. 19b also confirms that the phase error only slightly changes when the input power is increased.

Finally, it is worth showing how these parameters behave over the entire sweep of the input power level at three illustrative reflection coefficients. Under these load conditions summarized in Tab. IV, three distinct cases can be identified:

- 1) At  $\Gamma_{L1}$ ,  $\sigma_{b_2}$  is predominantly a result of  $\sigma_{\phi(b_2)}$ ,
- 2) At  $\Gamma_{L2}$ ,  $\sigma_{b_2}$  is a result of both  $\sigma_{|b_2|}$  and  $\sigma_{\phi(b_2)}$ ,
- 3) At  $\Gamma_{L3}$ ,  $\sigma_{b_2}$  is mainly a result of  $\sigma_{|b_2|}$ .

As shown in Fig. 20a,  $\sigma_{b_2}$  increases with the input power level  $P_{av}$ . This agrees with the results shown by previous paragraphs of this section. The behavior of  $\sigma_{|b_2|}$ , see Fig. 20b, is also in line with our expectations, thus, it's largest when  $\phi(\Gamma_L)$  is close to  $0^\circ$ . Then,  $\sigma_{|b_2|}$  decreases when  $\phi(\Gamma_L)$  approaches  $-90^\circ$ .  $\sigma_{\phi(b_2)}$  also acts as anticipated and we do not see significant variations of this parameters while increasing  $P_{av}$  for the particular  $\Gamma_L$ . As before, we observe that  $\sigma_{\phi(b_2)}$  is smallest when  $\phi(\Gamma_L)$  is around  $0^\circ$  while  $\sigma_{\phi(b_2)}$  reaches its peak when  $\phi(\Gamma_L)$  equals to around  $-90^\circ$ .

As expected considering the results shown in the previous sections, Fig. 20d shows that the standard deviation of  $P_{out}$

closely follows the uncertainty of  $b_2$ 's magnitude. Thus,  $\sigma_{P_{out}}$ , just like  $\sigma_{|b_2|}$ , is dependent on both  $|\Gamma_L|$  and  $\phi(\Gamma_L)$ .

Furthermore, by limiting the range of the output power  $P_{out}$ , we make its uncertainty analysis independent of large  $P_{out}$  changes over the whole Smith chart. In Fig. 21, we chose the  $P_{out}$  slice that is within the maximum  $\sigma_{P_{out}}$  but gives us enough measurement points for interpolation. Thus, we set the  $P_{out}$  range between 2.1 and 2.4 mW and identified 79 load points across input available powers  $P_{av}$  ranging from -20 to 0 dBm. Despite the limited  $P_{out}$  range,  $\sigma_{P_{out}}$  still closely follows the general behavior of uncertainty of the  $b_2$  and  $a_2$  waves' magnitudes, that is it increases towards the areas where  $|\Gamma_L|$  is high and  $\phi(\Gamma_L)$  is close to 0 or  $180^\circ$ . Thus, it may be concluded that the behavior of  $\sigma_{P_{out}}$  is independent of the  $P_{out}$  values.

It's also worth analyzing how the main uncertainty sources, delineated in Sec. III, contribute to the uncertainty of the  $b_2$  wave's magnitude and phase. In Tab. IV, we present the individual deviations when the DUT operates at  $P_{av} = 0$  dBm and under the three distinct load conditions already discussed in this section. In all the cases considered, the main causes of the uncertainty are the TRL and SOLT vector calibrations. Moreover, the TRL correction procedure's contribution to  $\sigma_{|b_2|}$  rapidly increases when  $\phi(\Gamma_L)$  gets close to  $0^\circ$ . In the case of  $\sigma_{\phi(b_2)}$ , the behavior is opposite. Thus, the behavior of  $\sigma_{\phi(b_2)}$  shown in Fig. 9b and 16b may be attributed to the TRL calibration scheme. Individual deviations due the SOLT calibration do not change with the varying load conditions. The errors originating from the probe alignment are also significant. The power meter measurements and the cable bending have small but definitely non-negligible contributions. Whereas, the inaccuracy caused by the characterization and repeatability of the HPR can practically be ignored.

## VII. SUMMARY OF THE RESULTS

Considering the results shown in the previous subsections, we can sum up the behavior of the  $b_2$  wave's uncertainties:

- 1)  $\sigma_{|b_2|}$  rapidly increases when  $\Gamma_L$  approaches the optimum load. Regardless of this, when  $\phi(\Gamma_L)$  is close to  $90^\circ$  or  $-90^\circ$ ,  $\sigma_{|b_2|}$  is low and practically independent of  $|\Gamma_L|$ ,



- 2)  $\sigma_{\phi(b_2)}$  is only directly dependent on  $|\Gamma_L|$  when  $\phi(\Gamma_L)$  is close to  $90^\circ$  or  $-90^\circ$ . When  $\phi(\Gamma_L)$  is close to  $0^\circ$  or  $180^\circ$ ,  $\sigma_{|b_2|}$  is low and practically independent of  $|\Gamma_L|$ ,
- 3) Behavior of  $\sigma_{b_2}$  is a result of the first two dependencies – this parameter increases with  $|\Gamma_L|$  for all  $\phi(\Gamma_L)$ ,
- 4)  $\sigma_{b_2}$  and  $\sigma_{|b_2|}$  are proportional to the  $P_{av}$  level,
- 5)  $\sigma_{\phi(b_2)}$  is virtually independent of the  $P_{av}$  levels.

Referring to the uncertainty in the  $a_2$  wave, we have the following inferences for the test case considered here:

- 1)  $\sigma_{|a_2|}$  closely follows  $\sigma_{|b_2|}$  and thus, increases as  $\Gamma_L$  gets close to the optimum load. However,  $\sigma_{|a_2|}$  is higher than  $\sigma_{|b_2|}$  at all the input power levels  $P_{av}$ ,
- 2)  $\sigma_{\phi(a_2)}$  is in inverse proportion to  $|\Gamma_L|$ .  $\sigma_{\phi(a_2)}$  decreases more rapidly when  $\phi(\Gamma_L)$  is close to  $0^\circ$  or  $180^\circ$ ,
- 3)  $\sigma_{a_2}$  has similar characteristic to the magnitude of  $b_2$  and as well achieves its maximum when  $\Gamma_L$  gets close to the optimum load. Furthermore,  $\sigma_{a_2}$  is higher than  $\sigma_{b_2}$ ,
- 4)  $\sigma_{a_2}$  and  $\sigma_{|a_2|}$  are proportional to the  $P_{av}$  level,
- 5)  $\sigma_{\phi(a_2)}$  is stable at all the  $P_{av}$  levels.

We assume that those findings are applicable also to devices other than the InP HBTs we used for performing the experiments. Furthermore, the dependencies of the  $b_2$  and  $a_2$  waves on the load reflection coefficient also affect figures of merit. By calculating the standard deviation of  $P_{out}$ , we have proven it's not only related to the the magnitude of the reflection coefficient, like in [17], but to its phase as well.

All the results presented in the paper may be of great value to the designers of microwave circuits. The knowledge of uncertainty in load-pull measurements could be used for extracting and validating nonlinear transistor models within a range of confidence [39]. Either using such models or measurement results directly, the designers can guarantee that circuits comply with the design requirements even in the worst-case scenarios [11]. If we could provide load-pull uncertainty data in real-time, another application could be adaptive sampling for modeling purposes [40]. In this case, the information provided by the uncertainty data could be used for safely choosing subsequent measurement points without violating the DUT's operational constraints [41]. Unfortunately, existing measurement platforms cannot provide real-time uncertainty in nonlinear measurements.

## VIII. CONCLUSION

In this paper, we evaluated uncertainty in large signal measurements under changing load conditions. In contrast to other relevant publications, we focused on frequency waves and investigated their residual errors. We included multiple sources of uncertainties in our analysis, such as passive calibration standards, power meter, NIST traceable phase calibration reference, and cable bending. For this purpose, we performed on-wafer load-pull measurements of the InP HBT transistors. Then, we were able to estimate the uncertainties in the frequency-domain waves by using the NIST Microwave Uncertainty Framework.

Since  $b_2$  and  $a_2$  are directly influenced by changing load conditions, we focused on their standard deviations of these

waves as well as their magnitudes and phases.  $b_2$  is particularly interesting as its uncertainty is dependent on both the phase and magnitude of  $\Gamma_L$ . We observe this behavior due to orthogonality of  $\sigma_{|b_2|}$  and  $\sigma_{\phi(b_2)}$  in relation to  $\Gamma_L$ . Interestingly,  $\sigma_{a_2}$  closely follows the magnitude of the  $b_2$ 's magnitude. Another noteworthy observation is that neither  $\sigma_{\phi(b_2)}$  nor  $\sigma_{\phi(a_2)}$  increases with the input power level even though standard deviations of these waves, as well as their magnitudes, rise when more power is delivered to the DUT. On top of this, uncertainties related to the  $a_2$  wave and its magnitude are higher than those affecting  $b_2$ .

In the paper, we also show the uncertainty of output power  $P_{out}$ , that is the power delivered to the load. This figure of merit illustrates how the uncertainty of performance quantities may be indirectly dependent on both the magnitude and phase of the load reflection coefficient. Thus, those relationships need to be considered during the development process if such performance figures are employed to design microwave circuits.

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